SurPass Advantage in Microlithography

- SurPass™ microlithography adhesion promoters provide maximum resist adhesion for advanced lithographic processes. Superior performance in optical and electron beam lithography applications.

- SurPass improves optical and e-beam resist adhesion on a broad range of substrate materials, including III-V materials, metals, and plastics.

- SurPass is a waterborne surface active agent that optimizes substrate surface energy for maximum resist adhesion, eliminating resist uplifting and undercutting during chemical processing.

- SurPass reduces the substrate zeta potential for improved resist process performance. Eliminates the pretreatment using organic solvents and wetting chemicals for increased throughput.

- Simple application via spray coating, spin coating or bath immersion makes SurPass ideal for application in new and existing manufacturing processes. Improved resist coating and process performance.

- SurPass is aqueous based and non-hazardous

Please contact us to receive additional product information and no-charge product samples for evaluation.